

**Amendments to the Specification:**

Please amend the specification as follows:

Please replace paragraph at page 1, lines 22-26, with the following rewritten paragraph:

Fig. 7 is a conceptual drawing of a cross section of a pattern for describing the tendency. A resist layer 73 adhering to the side surfaces of an aluminum interconnection pattern 72 on a substrate [[1]] 71 acts as a sidewall protection film. Concurrently, an altered resist layer 75 adheres also to the sidewalls of a resist pattern 74.